

	L #	Hits	Search Text
1	L1	1	("re36730").PN.
2	L2	564	(substrate or wafer) same (fiducial near mark)
3	L3	580	(substrate or wafer) same (fiducial near (plate or mark))
4	L4	26273	(mask or reticle) with (mark or align\$4)
5	L5	297	3 and 4
6	L6	185	5 and (355/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
7	L7	168	@ad<=20011129 and 6
8	L8	4987	(mask or reticle) with (mark)
9	L9	16367	(substrate or wafer) same align\$4 same (mask or reticle)
10	L10	222	3 and 9 and 8
11	L11	148	10 and (355/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
12	L12	133	@ad<=20011129 and 11

	L #	Hits	Search Text
13	L13	3	canon.as. and (fiducial near (plate or mark))
14	L14	4082	(substrate or wafer) same (alignment near (plate or mark))
15	L15	1154	(14 and 9) and (355/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
16	L16	1054	@ad<=20011129 and 15
17	L17	949	16 not 12
18	L18	683	(alignment adj mark) with (substrate or wafer) with (stage or table)
19	L19	293	17 and 18

pk
7/17/03